

	U	I	Document ID	Issue Date	Pages	Title	Current OR
1	<input type="checkbox"/>	<input type="checkbox"/>	US 6462346 B1	20021008	14	Mask inspecting apparatus and mask inspecting method which can inspect mask by using electron beam exposure system without independently mounting another mask inspecting apparatus.	250/492.2
2	<input type="checkbox"/>	<input type="checkbox"/>	US 5929454 A	19990727	36	Position detection apparatus, electron beam exposure apparatus, and methods associated with them	250/491.1
3	<input type="checkbox"/>	<input type="checkbox"/>	US 5892224 A	19990406	30	Apparatus and methods for inspecting wafers and masks using multiple charged-particle beams	250/310

	Current XRef	Retrieval Classif	Inv ntor	S	C	P	2	3	4	5
1	250/310		Kobinata, Hideo	<input checked="" type="checkbox"/>	<input type="checkbox"/>					
2			Muraki, Masato et al.	<input checked="" type="checkbox"/>	<input type="checkbox"/>					
3	250/307; 250/397		Nakasuji, Mamoru	<input checked="" type="checkbox"/>	<input type="checkbox"/>					

	Image Doc. Displayed	PT
1	US 6462346	<input type="checkbox"/>
2	US 5929454	<input type="checkbox"/>
3	US 5892224	<input type="checkbox"/>